

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	3282	204/298.14.ccls. or 1204/298.16.ccls. or 315/111.21.ccls. or 315/111.71.ccls. or 118/723R.ccls. or 118/723F.ccls.	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:22
L3	1137	l2 and ((magnet or magnetron or magnetic) with (field or flux)) same plasma	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:23
L4	2381	"l4" and (cathode or cathodic) and (anode or anodic)	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:23
L5	389	l3 and (cathode or cathodic) and (anode or anodic)	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:23
L6	291	l5 and (electric\$4 with (field or flux))	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:24
L7	263	l5 and (electric\$4 with (field or flux)) and electron	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:29
L8	26249	((magnet or magnetron or magnetic) with (field or flux)) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2010/12/16 15:29
L9	14036	(electric\$4 with (field or flux)) and electron	EPO; JPO; DERWENT	ADJ	ON	2010/12/16 15:30
L10	693	l8 and l9	EPO; JPO; DERWENT	ADJ	ON	2010/12/16 15:30
L11	101	l8 and l9 and (cathode or cathodic) and (anode or anodic)	EPO; JPO; DERWENT	ADJ	ON	2010/12/16 15:30
L12	44723	((magnet or magnetron or magnetic) with (field or flux)) and plasma	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:34
L13	4494	((((magnet or magnetron or magnetic) with (field or flux)) and plasma). clm.	US-PGPUB; USPAT	ADJ	ON	2010/12/16 15:34

L14	597	((magnet or magnetron or magnetic) with (field or flux)) and plasma and (cathode or cathodic) and (anode or anodic)).clm.	US-PGRUB; USPAT	ADJ	ON	2010/12/16 15:34
L15	187	((magnet or magnetron or magnetic) with (field or flux)) and plasma and (cathode or cathodic) and (anode or anodic) and (electric\$4 with (field or flux)) and electron).clm.	US-PGRUB; USPAT	ADJ	ON	2010/12/16 15:34
L16	95	((magnet or magnetron or magnetic) with (field or flux)) and plasma and (cathode or cathodic) and (anode or anodic) and (electric\$4 with (field or flux)) and electron and (substrate or workpiece or workpiece or object or target or wafer or semiconductor)).clm.	US-PGRUB; USPAT	ADJ	ON	2010/12/16 15:35
S1	14	((("4963524") or ("5224441") or ("5364665") or ("4863756") or ("5627435") or ("6066826") or ("6077403") or ("4631106") or ("4761219") or ("4853102") or ("5099790") or ("5225024") or ("5437725") or ("5900284"))).PN.	US-PGRUB; USPAT	OR	OFF	2009/06/01 08:50
S2	15	((("4963524") or ("5224441") or ("5364665") or ("4863756") or ("5627435") or ("6066826") or ("6077403") or ("4631106") or ("4761219") or ("4853102") or ("5099790") or ("5225024") or ("5437725") or ("20040110388")) or	US-PGRUB; USPAT	OR	OFF	2009/06/01 08:53

		("5900284")).PN.				
S3	49	("4871580" "5466295" "4911784" "5232569" "5413663" "4854263" "5376211" "5505780" "5660671" "5773100" "5888338" "6014943" "6040022" "6187160" "6196155" "4243505" "4299678" "4324631" "4426267" "4772513" "4971651" RE33530 "4996077" "5234560" "5320704" "5635087" "5659276" "5674321" "5685959" "5831335" "5900284" "6042707" "6054063" "6055929" "6086796" "6099706" "6106682" "6126790" "6211535" "6211535" "4370176" "4401054" "4434037" "4471003" "4487162" "4500408" "4544468" "4581118" "4585541" "4615944"). pn.	US-PGRUB; USPAT	OR	ON	2009/06/01 11:12
S4	1	10/314497.app.	US-PGRUB; USPAT	ADJ	ON	2009/06/01 11:49
S5	0	kobayashi.in. (sputter or sputtering)	US-PGRUB; USPAT	ADJ	ON	2009/12/10 19:11
S6	2068	kobayashi.in. and (sputter or sputtering)	US-PGRUB; USPAT	ADJ	ON	2009/12/10 19:11
S7	683	kobayashi.in. and (sputter or sputtering) and (magnetron or magnet or magnetic)	US-PGRUB; USPAT	ADJ	ON	2009/12/10 19:11
S8	0	kobayashi.in. and (sputter or sputtering) and (magnetron or magnet or magnetic) and shiel	US-PGRUB; USPAT	ADJ	ON	2009/12/10 19:11
S9	205	kobayashi.in. and (sputter or sputtering) and (magnetron or magnet or magnetic) and shield	US-PGRUB; USPAT	ADJ	ON	2009/12/10 19:11

S10	16	kobayashi.in. and (sputter or sputtering) and (magnetron or magnet or magnetic) and shield and ((substrate or wafer) with bias)	US-PGPUB; USPAT	ADJ	ON	2009/12/10 19:12
S11	109	andoe and cathode and (magnet or magnetron or magnetic) and (substrate or wafer) and (magnetic with (field or flux))	US-PGPUB; USPAT	ADJ	ON	2009/12/11 13:46
S12	8374	anode and cathode and (magnet or magnetron or magnetic) and (substrate or wafer) and (magnetic with (field or flux))	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:02
S13	2447	anode and cathode and (magnet or magnetron or magnetic) and (substrate or wafer) and (magnetic with (field or flux)) and ((alternating near1 current) or ac)	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:03
S14	1755	anode and cathode and (magnet or magnetron or magnetic) and (substrate or wafer) and (magnetic with (field or flux)) and ((alternating near1 current) or ac) and electron	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:03
S15	1145	anode and cathode and (magnet or magnetron or magnetic) and (substrate or wafer) and (magnetic with (field or flux)) and ((alternating near1 current) or ac) and electron and (electric with (field or flux))	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:03
S16	772	S15 and ((substrate or wafer) same (magnet or magnetron or magnetic))	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:04
S17	581	S15 and ((substrate or wafer) with (magnet or magnetron or magnetic))	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:04

S18	134	S15 and ((substrate or wafer) with (magnet or magnetron or magnetic) with (holder or pedestal or chuck or support))	US-PGPUB; USPAT	ADJ	ON	2009/12/11 16:04
S19	1	("4842683").PN.	US-PGPUB; USPAT	OR	OFF	2009/12/11 16:11
S20	1488	(annular with (magnet or magnetic or magnetron)) same (racetrack or track or race-track)	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:07
S21	1294	(annular with (magnet or magnetic or magnetron)) with (racetrack or track or race-track)	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:08
S22	37305	plasma with (processing or processor)	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:15
S23	18823	substrate with web	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:15
S24	279	S22 and S23	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:16
S25	81	S22 and S23 and (convey or conveyor)	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:16
S26	15	S22 and (S23 same (convey or conveyor))	US-PGPUB; USPAT	ADJ	ON	2009/12/14 16:16
S27	1	wo-03085693-\$.did.	DERWENT	ADJ	ON	2009/12/14 16:42
S28	1	2003-779635.NRAN.	DERWENT	ADJ	ON	2009/12/14 16:43
S29	0	substrate and web and (convey or conveyor) and plasma	JPO	ADJ	ON	2009/12/14 16:46
S30	12	substrate and web and plasma	JPO	ADJ	ON	2009/12/14 16:46
S31	27	((JOHN) near2 (MADDOCKS)).INV.	US-PGPUB; USPAT	ADJ	ON	2009/12/14 17:50

S32	19	("2146025" "3282815" "4356073" "4407894" "4445997" "4624767" "4631106" "4761219" "4767516" "4784739" "4842683" "4853102" "4863756" "4874497" "4963524" "5000834" "5099790" "5135819" "6911779").FN.	US-PGPUB; USPAT	OR	ON	2010/06/01 17:10
S33	36	("2146025" "3282815" "4356073" "4407894" "4445997" "4624767" "4631106" "4761219" "4767516" "4784739" "4842683" "4853102" "4863756" "4874497" "4963524" "5000834" "5099790" "5135819" "6911779").FN. or ("5224441" "5225024" "5328583" "5364665" "5437725" "5439574" "5527394" "5627435" "5874807" "5900284" "5945008" "6066826" "6077403" "6103074" "6190496" "6287687" "6819053").pn.	US-PGPUB; USPAT	OR	ON	2010/06/01 17:17
S34	41	("2146025" "3282815" "4356073" "4407894" "4445997" "4624767" "4631106" "4761219" "4767516" "4784739" "4842683" "4853102" "4863756" "4874497" "4963524" "5000834" "5099790" "5135819" "5224441" "5225024" "5328583" "5364665" "5437725" "5439574" "5527394" "5627435" "5874807" "5900284" "5945008"	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/06/01 18:05

		"6066826" "6077403" "6103074" "6190496" "6287687" "6819053"). PN. OR ("6911779"). URPN.				
S35	1316	(AC or (alternating near1 current)) with (substrate or wafer or workpiece or work- piece)	JPO	ADJ	ON	2010/06/02 17:36
S36	1	("6911779").PN.	US-PGPUB; USPAT	OR	OFF	2010/12/14 14:52
S37	0	10/5712174.app.	US-PGPUB; USPAT	ADJ	ON	2010/12/14 15:00
S38	1	10/571214.app.	US-PGPUB; USPAT	ADJ	ON	2010/12/14 15:00

EAST Search History (I nterference)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L17	57	((magnet or magnetron or magnetic) with (field or flux)) and plasma and (cathode or cathodic) and (anode or anodic) and (electric\$4 with (field or flux)) and electron and (substrate or workpiece or work-piece or object or target or wafer or semiconductor)).clm.	USPAT; UPAD	ADJ	ON	2010/12/16 15:43

12/ 16/ 2010 3:51:30 PM

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